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(72) Inventors: TOMPA, Gary, S. [US/US]; 43 Franklin Drive, Belle Mead, NJ 08502 (US). RICE, Catherine, E. [US/US]; 1956 Church Street, Scotch Plains, NJ 07076 (US). SBROCKEY, Nicholas, M. [US/US]; 642 Gatestone Street, Gaithersburg, MD 20878 (US). HOERMAN, Brent, H. [US/US]; 42 Easton Avenue, New Brunswick, NJ 08901 (US). PROVOST, L., Gary [US/US]; 49 Douglas Road, Glen Ridge, NJ 07028 (US). SUN, Shangzhu [US/US]; 29 White Meadow Road, Hillsborough, NJ 08844 (US).

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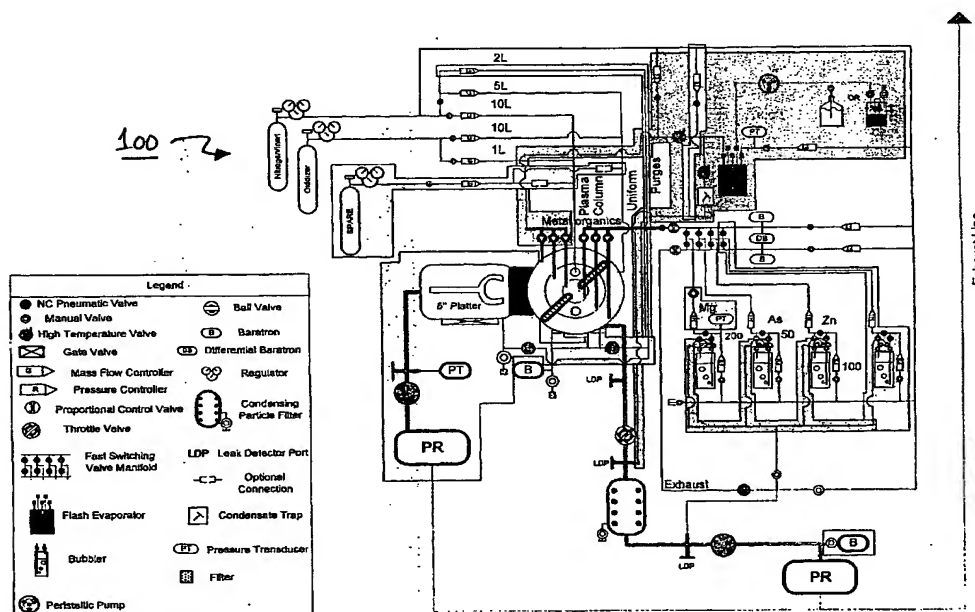
(74) Agent: YU-JAHNES, Lock, See; Lowenstein Sandler PC, 65 Livingston Avenue, Roseland, NJ 07068 (US).

(71) Applicant (for all designated States except US): STRUCTURED MATERIALS INDUSTRIES, INC. [US/US]; 201 Circle Drive North, Suite 102/103, Piscataway, NJ 08854-3723 (US).

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(54) Title: SYSTEM AND METHOD FOR FORMING MULTI-COMPONENT FILMS



(57) Abstract: A system and a method for depositing films of a multi-component material by MOCVD utilizes a flash evaporator for providing vaporized reactant material at a high flow rate. The high flow rate enables film deposition to occur at a higher deposition rate than what is possible with conventional MOCVD systems. The system may be a single-chamber system or part of a multiple-chamber system. The multiple-chamber system allows multi-layer structures to be deposited and/or processed *in situ*.



TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

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